

AMENDMENTS TO THE CLAIMS

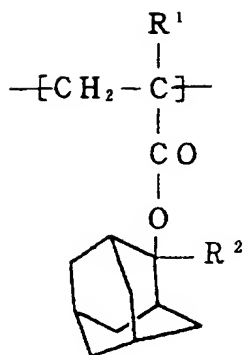
1. (Original) A composition for formation of an antireflection film prepared by dissolving, in an organic solvent, (A) a ladder-type silicone copolymer consisting of (a₁) 10-90% by moles of (hydroxyphenylalkyl)silsesquioxane units, (a₂) 0-50% by moles of (alkoxyphenylalkyl)silsesquioxane units and (a₃) 10-90% by moles of alkyl- or phenylsilsesquioxane units, (B) an acidgenerating agent capable of generating an acid by heat or light and (C) a crosslinking agent and having a characteristic to be capable of forming an antireflection film of which the optical parameter (k value) relative to ArF lasers is in the range of 0.002-0.95.

2. (Original) The composition for formation of an antireflection film described in Claim 1 which further contains (D) a linear polymer in addition to the component (A), component (B) and component (C).

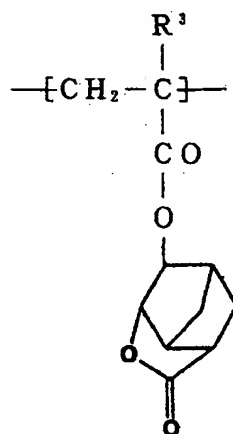
3. (Original) The composition for formation of an antireflection film described in Claim 2 in which the said (D) linear polymer is a polymer containing hydroxyl group-containing (meth)acrylic acid ester units.

4. (Original) The composition for formation of an antireflection film described in Claim 3 in which the said (D) linear polymer is a polymer containing (meth)acrylic acid ester units having hydroxyl group-containing aliphatic polycyclic groups.

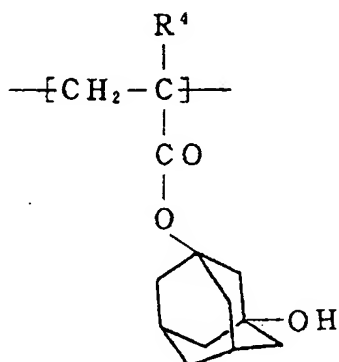
5. (Original) The composition for formation of an antireflection film described in Claim 3 in which the said (D) linear polymer is a linear copolymer consisting of 10-60% by moles of the constituent units (d₁) represented by the general formula,



(In the formula, R' is a hydrogen atom or a methyl group and R² is an alkyl group), 30-80% by moles of the constituent units (d₂) represented by the general formula,



(R³ in the formula is a hydrogen atom or a methyl group) and 10-50% by moles of the constituent units (d₃) represented by the general formula,



(R⁴ in the formula is a hydrogen atom or a methyl group).

6 to 9. (Canceled)